

Lucida™ GD series

High-throughput atomic layer deposition system for OLED displays

Features

- Al₂O₃ thin film encapsulation for OLED
- Al₂O₃ barrier layer for flexible substrates
- WVTR(water vapor transmission rate) of 5.3×10^{-6} g/m² day (@ 30nm Al₂O₃/PEN substrate)
- Applications of mass-production
- Industrial fully-automated production equipment
- High throughput : up to 30 panels/hour of 6G panels(1500x1850 mm²)

Specifications

Model	Material	Wafer size (mm ²)	Thickness (nm)	Throughput (panel/hour)
Lucida™ GD 200	Al ₂ O ₃	370x470	30	30
Lucida™ GD 400H	Al ₂ O ₃	460x730	30	30
Lucida™ GD 550Q	Al ₂ O ₃	650x750	30	30
Lucida™ GD 600	Al ₂ O ₃	1500x1850	30	30

※ We could be processed that substrate sizes of a variety



Process module for Lucida™ GD series



Cluster system for Lucida™ GD series